

Title (en)

METHOD FOR MECHANOCHEMICAL POST-POLISH CLEANING OF AN OXIDE OR NITRIDE LAYER DEPOSITED ON A SUBSTRATE

Title (de)

VERFAHREN ZUR REINIGUNG EINER OXYD- ODER NITRIDSCHICHT AUF EINEM SUBSTRAT NACH EINEM CHEMISCH-MECHANISCHEN POLIEREN

Title (fr)

PROCEDE DE NETTOYAGE POST-POLISSAGE MECANO-CHEMIQUE D'UNE COUCHE D'OXYDE OU DE NITRURE DEPOSEE SUR UN SUBSTRAT

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Abstract (en)

[origin: FR2769248A1] An oxide or nitride layer is subjected to post chemical-mechanical polishing (CMP) cleaning by spraying with an aqueous ammonia and hydrogen peroxide solution and then an aqueous hydrofluoric and hydrochloric acid solution to produce a low etched thickness. A post-CMP cleaning process for an oxide or nitride layer on a substrate comprising spraying the layer with an aqueous solution of ammonia and hydrogen peroxide (NH₄OH : H₂O₂ : H₂O) and then with an aqueous solution of hydrofluoric and hydrochloric acids (HF : HCl : H₂O) to produce a total etched layer thickness of 4-6 nm.

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